

Comparison between HovaCAL models

<p style="text-align: center;">HovaCAL MFM</p> 	<p style="text-align: center;">HovaCAL Quick</p> 
<p>End-Use</p> <p>Flexible system for research and stack testing applications. System generates hot-wet vapors of reactive mixtures for HgCl₂, NH₃, HCl, HF etc.</p>	<p>End-Use</p> <p>Optimized system for Mercury CEMS operating in a plant environment. System generates hot-wet vapors of HgCl₂ only.</p>
<p>Liquid Flow Measurement</p> <p>Liquid flow rates can be measured with an external balance or an internal mass flow meter.</p>	<p>Liquid Flow Measurement</p> <p>Liquid flow rates are measured with an internal mass flow meter.</p>
<p>Flow Ranges – Standard</p> <p>Carrier Gas: Variable between 3 to 10 lit/min</p> <p>Liquid: Variable between 0.01 to 8 ml/min with external balance, 0.05 to 3 ml/min with internal mass flow meter</p> <p>Total Gas Mixture: Up to 16 lit/min</p> <p>Flow Ranges - Optional</p> <p>High total gas flow up to 25 lit/min</p> <p>Additional Feature</p> <p>Gas mixer function with 2, 3, 4 or 5 gas channels</p>	<p>Flow Ranges – Standard</p> <p>Carrier Gas: Fixed at one value between 3 to 10 lit/min</p> <p>Liquid: Fixed at one value between 0.05 to 3 ml/min with internal mass flow meter</p> <p>Total Gas Mixture: Up to 16 lit/min</p> <p>Flow Ranges - Optional</p> <p>Variable total gas flow 3 to 10 lit/min</p> <p>Variable total gas flow 8 to 25 lit/min</p> <p>Variable liquid flow rate 0.05 to 3 ml/min</p>
<p>Configuration</p> <p>Standard Restek Silicosteel or similar coating for evaporator, spare parts kit and short heated connecting tube.</p> <p>Standard desktop housing, optional portable field case.</p>	<p>Configuration</p> <p>Standard Restek Silicosteel or similar coating for evaporator, spare parts kit and short heated connecting tube.</p> <p>Standard desktop housing, optional portable field case.</p>
<p>User Interface</p> <p>Standard touch-screen and PC interface software</p>	<p>User Interface</p> <p>Standard touch-screen and PC interface software</p>

Version 1.57 – Subject to technical changes